



[WeA3] Nanoscale Thin Film Deposition V

Session Date	November 12 (Wed.), 2025
Session Time	16:05-17:45
Session Room	Room A (Capri Room, 2F)
Session Chair	Prof. Woo-Jae Lee (Pukyong National Univ., Korea)

[WeA3-1] [Invited] 16:05-16:35

Atomically Ordered ALD Oxide Semiconductors for High-Mobility, Low-Temperature Logic and BEOL Integration

Jin-Seong Park (Hanyang Univ., Korea)

[WeA3-2] [Invited] 16:35-17:05

High-Performance Transparent Conducting Oxides via Nano-Textured Substrates and Ag Interlayer

Sung-Yong Mun, Dong-Hwi Lee, and Young-Rae Cho (Pusan Nat'l Univ., Korea)

[WeA3-3] 17:05-17:25

Theoretical Study of Radical Decomposition of Low GWP Alternative Gases and Fluorocarbon Film Formation on SiO₂

Minji Kim and Sangheon Lee (Ewha Womans Univ., Korea)

[WeA3-4] 17:25-17:45

Work Function Modulation of Chlorine-Free TiAlN Films through Controlled Al Incorporation by Thermal ALD

Gyeong Min Jeong, Hae-dam Kim, and Jin-Seong Park (Hanyang Univ., Korea)